

Plasma & Sputtering Sources

THIN FILM CONSULTING 



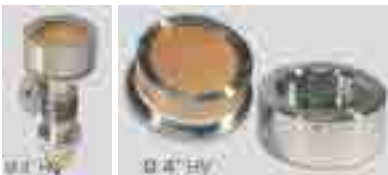
Planar Magnetrons by THFC

The unique IONIX[®] magnetron sputtering sources have a flexible architecture to cope with the partially contradicting performance requirements of modern vacuum coating technology. The IONIX[®] concept is based on maximum reliability, adaptable magnet array layout and versatile design to fit with customer's specific applications.

Since January 2017 robeko is sales agent for Thin Film Consulting.

High Vacuum Round Magnetrons

For R + D and small scale production







IONIX[®] round magnetrons are available in target diameters of 1.25" to 10" and include standard KF/ISO interfaces for use with virtually any type of vacuum chamber installation.

UHV Round Magnetrons

For scientific research



IONIX[®] UHV magnetrons are available in target diameters of 1" to 8". Rectangular UHV sources are available on request.

-  Metallic sealing vacuum-to-air
-  No seals vacuum-to-water
-  Bakeable 200°C
-  Flange mount and internal mount design

Flange Mount Magnetron Assy's

IONIX[®] flange assemblies plug-in solutions:

-  Target Ø 1" - Ø 6" HV and UHV
-  Pneumatic shutter
-  Argon distribution
-  Z-adjustment
-  +/- 45° tilt
-  DN 100 ISO - DN 200 ISO
-  DN 63 CF bis DN 200 CF

